

AVSでの海外論文発表

CF₃⁺およびCl⁺による酸化物および窒化物のエッチングの分子動力学シミュレーション



目で見ると
海外論文発表

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Molecular Dynamics Simulation of Oxide and Nitride Etching by CF₃⁺ and Cl⁺

Key Words : molecular dynamics simulation, plasma etching

<参加会議名>

American Vacuum Society 68th International Symposium & Exhibition (AVS68)

<開催場所>

David L. Lawrence Convention Center, Pittsburgh, Pennsylvania, United States

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<発表タイトル>

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The theme of AVS 68th is "Imperfectly Perfect Material" which reflects the cross-cutting importance of defects in materials across the different programs in AVS.

I presented our research in the session for Modelling of Plasmas and Plasma Driven Processes, and Machine Learning as shown in the images below. My presentation was well received by the audience. I was also grateful to be chosen as one of the four finalists of the prestigious Plasma Science and Technology Division (PSTD) Coburn and Winters (C&W) Student Award. Though I did not win, being one of the finalists is a great achievement.

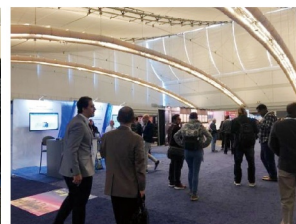
Aside from the various invited talks, oral presentations, and poster presentations, AVS also held an exhibit by various industries related to

vacuum technology. Having the opportunity to talk to people from the industries is a great way to see how the research done in the academe is seen in the industry. The exhibitors provided some fun activities for the attendees such as free caricatures, foosball tournament, and the 3-day raffle draw where some were able to win prizes such as a MacBook Pro laptop. I unfortunately did not win, but I was able to avail the free caricature. With the great number of attendees, I was able to meet former colleagues as well as new people. I also had the opportunity to meet in person one of our collaborators that I have only been communicating online. Being able to attend the conference in person is a huge encouragement in completing my research, especially after the challenges caused by the pandemic.

Overall, the conference was an invaluable experience and a great learning opportunity.



Presentation



Industry Exhibits in Hall

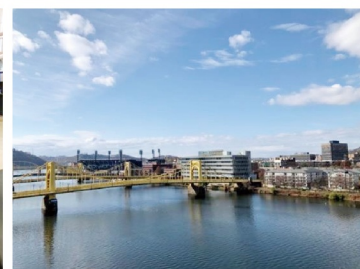


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Free Caricature



View at the Rooftop of the Venue